

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Masaharu Nagai et al.                      Art Unit : Unknown  
Serial No. : New Application                              Examiner : Unknown  
Filed : October 29, 2003  
Title : METHOD FOR REMOVING RESIST PATTERN AND METHOD FOR  
MANUFACTURING SEMICONDUCTOR DEVICE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**PETITION TO ACCEPT COLOR PHOTOGRAPHS**

Applicants hereby petition under 37 CFR §1.84(b)(2) that the color photographs filed in the application be accepted.

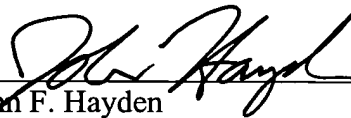
The subject matter of the invention relates to a method for removing a resist pattern that is formed in a photolithography process and a method for manufacturing a semiconductor device by using the method for removing a resist pattern. The color photographs in figures 7A-7H and 8A-8C are necessary to accurately and clearly depict the subject matter sought to be patented.

Enclosed is a check for \$130 to cover the fee required under 37 CFR §1.17(i), three (3) sets of the color photographs, a black and white set of the photographs and an amendment to insert a reference to the color photographs into the specification.

Please apply any other charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: October 29, 2003

  
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